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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHO ET AL. Atty. Ref.: 4105-73

Appl. No. Unknown TC/A.U. Unknown

Filed: February 21, 2006 Examiner: Unknown

For: FERROELECTRIC THIN-FILM PRODUCTION METHOD, VOLTAGE-APPLICATION ETCHING APPARATUS, FERROELECTRIC CRYSTAL THIN-FILM SUBSTRATE, AND FERROELECTRIC CRYSTAL WAFER

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February 21, 2006

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

PRELIMINARY AMENDMENT

In order to place the above-identified application in better condition for examination, please amend the application as follows: